

19/CPA
7-1-00
Harrison

CONTINUED PROSECUTION APPLICATION (CPA) UNDER 37 C.F.R. § 1.53(d) REQUEST TRANSMITTAL		
Address to: Assistant Commissioner for Patents Box CPA Washington, D.C. 20231	Attorney Docket No.:	303.573US1
	First Named Inventor:	Gurtej Singh Sandhu
	Express Mail No.:	EL584211141US
	Total Pages (if by fax):	0

This is a request for filing a continuation application under 37 CFR § 1.53(d) of prior application Serial No. 08/636,069, filed on April 22, 1996, entitled METHOD TO REDUCE FIXED CHARGE IN CVD OZONE DEPOSITED FILMS.

The above-identified prior application in which no abandonment of, or termination of, proceedings has occurred, is hereby expressly abandoned as of the filing date of this request for a CPA. Please use all the contents of the prior application file wrapper, including the drawings, as the basic papers for the new application. (37 CFR 1.53(b) must be used for continuation-in-part applications or for applications where the prior application is not to be abandoned.)

1. ☐ Enter the amendment previously filed on ☐ under 37 CFR 1.116, but unentered, in the prior application.
2. ☒ A Preliminary Amendment (9 pages) is enclosed.
3. ☐ This application is filed by fewer than all the inventors named in the prior application, 37 CFR 1.53(d)(4).
 - a. ☐ **DELETE** the following inventor(s) named in the prior nonprovisional application:

 - b. ☐ The inventor(s) to be deleted are set forth on a separate sheet attached hereto.
4. ☐ A new power of attorney is enclosed.
5. ☐ Information Disclosure Statement is enclosed.
 - a. ☐ Form(s) 1449
 - b. ☐ Copies of IDS Citations

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fee on front page

The filing fee is calculated below on the basis of the claims existing in the prior application as amended at 1 and 2 on the previous page:

	No. Filed	No. Extra	Rate	Fee
TOTAL CLAIMS	29 - 20 =	9	x 18 =	\$162.00
INDEPENDENT CLAIMS	12 - 3 =	9	x 78 =	\$702.00
[] MULTIPLE DEPENDENT CLAIMS PRESENTED				\$0.00
BASIC FEE				\$690.00
TOTAL				\$1,554.00

6. ☐ Small Entity Status:

- a. ☐ A small entity statement is enclosed.
b. ☐ A small entity statement was filed in the prior nonprovisional application and such status is still proper and desired.
c. ☐ Is no longer claimed.

7. ☐ A check in the amount of \$0.00 is attached to pay the filing fee.

8. ☒ The Commissioner is hereby authorized to charge the filing fee of \$1,554.00 to Deposit Account No. 19-0743.

9. ☒ A petition for extension of time in the prior application is enclosed along with a check in the amount of \$380.00 to pay the extension fee.

10. ☐ Other : _____

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"Express Mail" mailing label number E1584211141US
I hereby certify that this paper or fee is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 C.F.R. 1.10 on the date indicated above and is addressed to Box CPA, Assistant Commissioner for Patents, Washington, D. C. 20231

Todd Bowie
Printed Name

Todd Bowie
Signature

S/N 08/636,069

7-31-00 Harrison
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Gurtej Singh Sandhu et al. Examiner: Matthew Wipple
Serial No.: 08/636,069 Group Art Unit: 2813
Filed: April 22, 1996 Docket: 303.573US1
Title: METHOD TO REDUCE FIXED CHARGE IN CVD OZONE DEPOSITED FILMS

PRELIMINARY AMENDMENT & RESPONSE

Box CPA
Assistant Commissioner for Patents
Washington, D.C. 20231

JUL 10 2000

Preliminary to the Examination of the present Continuing Prosecution Application, and in response to the Final Office Action mailed on December 2, 1999, in the parent case, please amend the above-identified patent application as follows.

IN THE CLAIMS

Please delete claims 7/10 without prejudice or disclaimer. Please amend claims 1, 31, 42, 43, 45, 46-48 and 50-53 as follows:

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①

1. (Twice amended) A chemical vapor deposition (CVD) process for depositing borophosphosilicate glass films on a substrate surface, the process comprising:
disposing the substrate within a chemical vapor deposition reaction chamber;
heating the substrate to a temperature within a range of at least 480°C to about 700°C;
introducing a gas volume of SiO₂ precursors into the chamber;
admitting a gas volume of ozone into the chamber;
admitting a dopant source for phosphorus into the chamber;
admitting a dopant source for boron into the chamber; and
[illuminating, with a source of high intensity light, the volume of gas located above the substrate surface]

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